Serial No. 10/016,562

OFFICIAL

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Chang-Lin Hsieh.

Serial No.:

10/016,562

Filed:

12/12/2001

Title:

Process for Selectively Etching Dielectric Layers

Art Unit:

1765

Examiner:

Deo, Duy Vu Nguyen

Docket No.: 004544/ALRT/ETCH/DICP

VIA FACSIMILE 703-872-9311 Mail Stop Box AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## RESPONSE TO OFFICE ACTION

Sir:

This is responsive to the final Office Action mailed March 4, 2004 in the above matter.

251 North Avenue West, 2nd Floor Westfield, NJ 07090

13164 Lazy Glen Lane Oak Hill, Virginia 20171

## Mayer, Fortkort & Williams, PC **Attorneys At Law**

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	Dav	id Bonham			
	Sinc	erely,			
Re:	In connection with the prosecution in Serial. No. 10/018,562, please find enclosed a response to the Office Action mailed March 4, 2004.				
Phone	:			Dates	6/4/2004
Faxc	703	872-9311		Total page	s: 17
Тоя	Соп	missioner for Paten		From:	David Bonham (703) 433-0510

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